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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re application of: Shrinivasan et al.

Attorney Docket No.:
NOVLP029/NVLS-000495

Application No.: 10/067,520

Examiner: Not yet assigned

Filed: February 5, 2002

Group: 2811

Title: APPARATUS AND METHODS FOR
PROCESSING SEMICONDUCTOR
SUBSTRATES USING SUPERCRITICAL
FLUIDS

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail to: Commissioner for Patents, Washington, DC 20231 on May 31, 2002.

Signed: _____

Tara Hayden

INFORMATION DISCLOSURE STATEMENT 37 CFR §§1.56 AND 1.97(b)

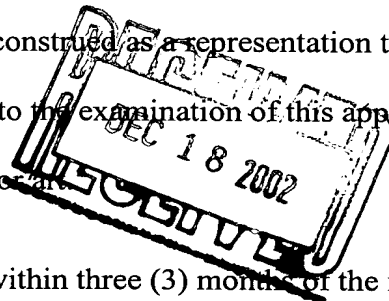
Commissioner for Patents
Washington, DC 20231

Dear Sir:

The references listed in the attached PTO Form 1449, copies of which are attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure



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Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NVLSP029).

Respectfully submitted,

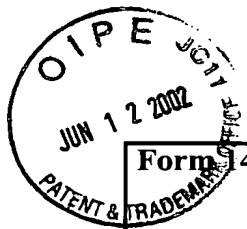
BEYER WEAVER & THOMAS, LLP

A handwritten signature in black ink, appearing to read "Brian D. Griedel". The signature is fluid and cursive, with the first name "Brian" being more prominent than the last name "Griedel".

Brian D. Griedel

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Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. NOVLP029/000495	Application No.: 10/067,520
	Applicant: Shrinivasan et al. Filing Date February 5, 2002	Group 2811

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	A	Biberger et al., "High Pressure Processing Chamber for Semiconductor Substrate", Pub. No. US 2002/0046707 A1, Pub. Date: April 25, 2002, Appl. No.: 09/912,844, Filed: July 24, 2001, pp. 1-19.
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.